

**Amendments to the Specification**

Please replace the paragraph beginning at page 12, line 4, with the following rewritten paragraph:

As shown in FIG. 7, each aperture 12 is a communicating hole defined by a substantially rectangular larger hole 19a and a substantially ~~rectangular smaller hole 22~~ rectangular smaller hole 19b that communicate with each other. The larger hole opens in that surface of the main mask 14 on the phosphor screen side. The smaller hole opens in that surface of the main mask on the electron gun side. In each of the apertures that, among the other apertures 12, are situated on the peripheral side of the effective portion 13, a center C1 of the larger hole 19a is deviated relatively from a center C2 of the smaller hole 19b by an offset  $\Delta$  on the peripheral side of the effective portion. The offset  $\Delta$  becomes greater for the apertures that are situated nearer to the peripheral side of the effective portion 13. The electron beams are obliquely incident upon the apertures 12 at the peripheral portion of the main mask 14. Therefore, each electron beam is restrained from running against and being reflected by the inner surface of each aperture 12 and from producing useless light emission on the picture plane after having passed through the smaller hole 19b. The larger hole 19a is offset with respect to the smaller hole 19b in both the directions of the minor axis Y and the major axis X of the main mask 14.